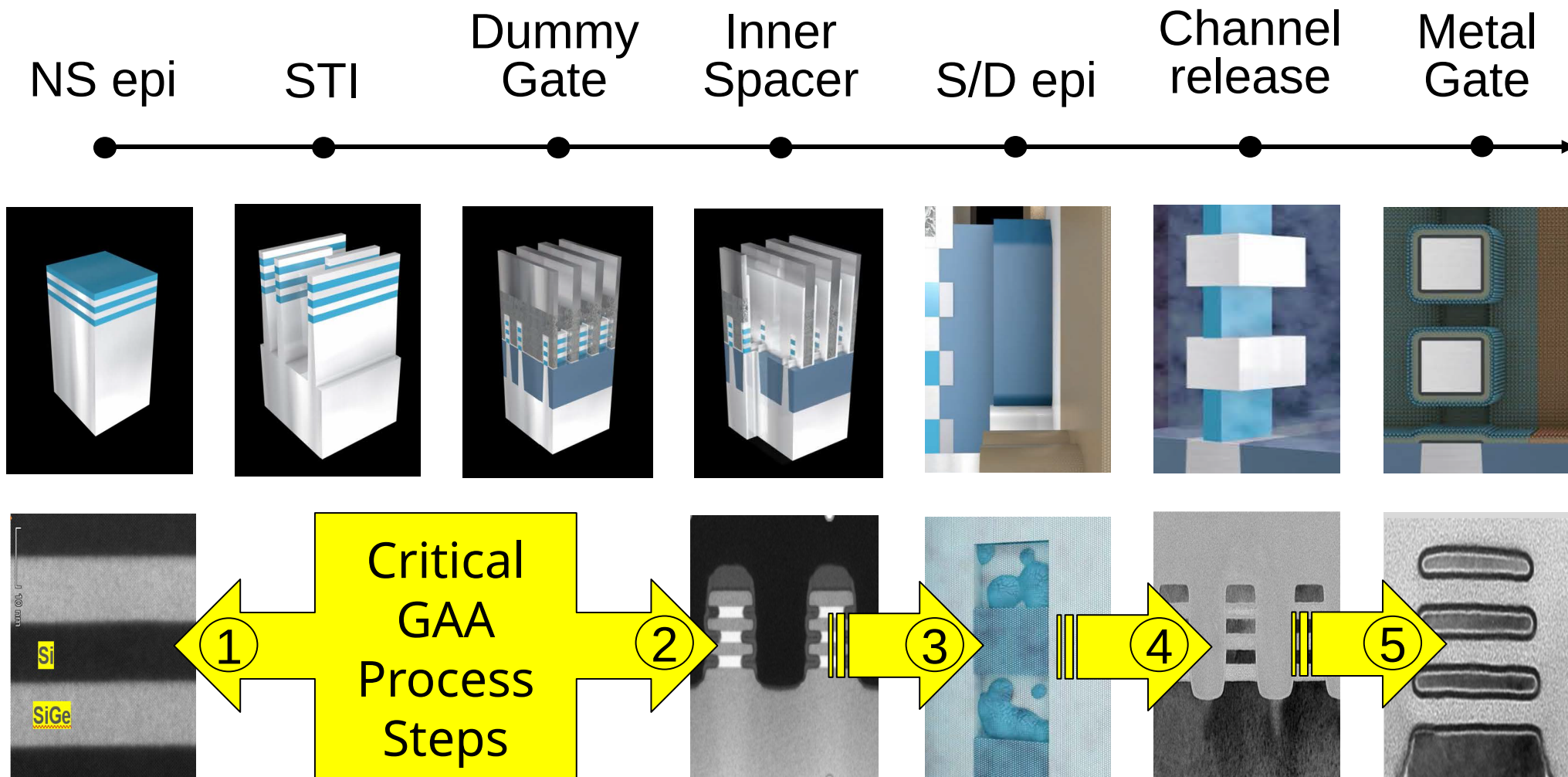




# Photo-Modulated Reflectance for Gate-All- Around Metrology



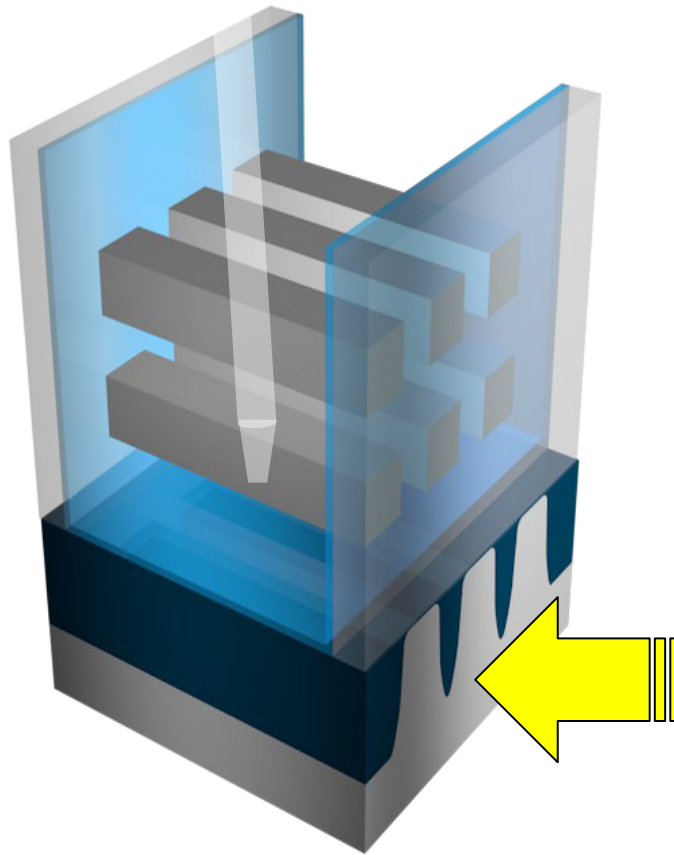
# Gate-All-Around (GAA) Process Flow:



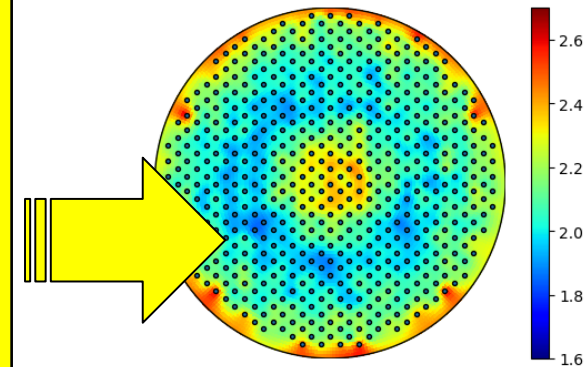
Images courtesy

# eBeam Metrology/Inspection for GAA:

eBeam addresses 2 of the 5 Critical GAA Steps:  
Inner Spacer & Channel Release

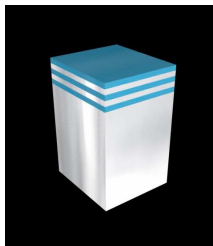


Challenges with  
3D structures &  
Need for Massive  
Sampling (local &  
wafer scale)...



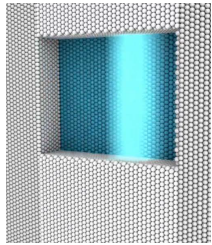
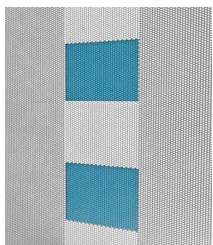
# Metrology Missing for 3 Critical GAA Steps:

NS epi

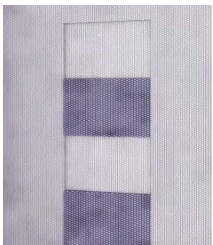


Metrology for SiGe/Si Superlattice??

Inner Spacer

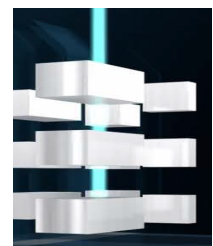
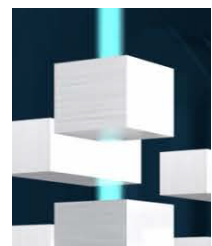
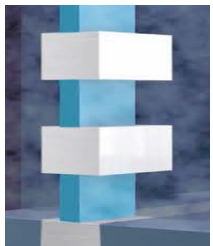


S/D epi

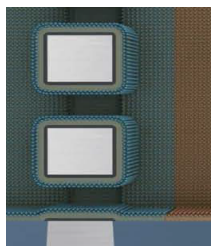


Metrology for SiGe, Doping Profile??

Channel release



Metal Gate



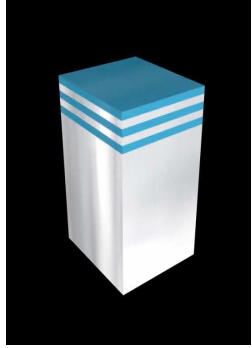
Metrology for Work Function ( $V_t$  adjust)??

Images courtesy



# Case of the Missing Metrologies: GAA

NS  
epi



- Ellipsometry for SL thicknesses, Ge%  $\Rightarrow$  unstable fits
- HR-XRD for SL thicknesses, Ge%  $\Rightarrow$  slow & analytical

KPM is mobility of Si channel: no metrology

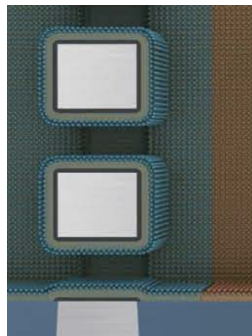
S/D  
epi



- $\mu$ -4PP  $\Rightarrow$   $\sim 120\mu\text{m}$  spot size, contact...
- Hall Effect  $\Rightarrow$  accurate but destructive...

KPM is S/D doping profile: no metrology

Metal  
Gate



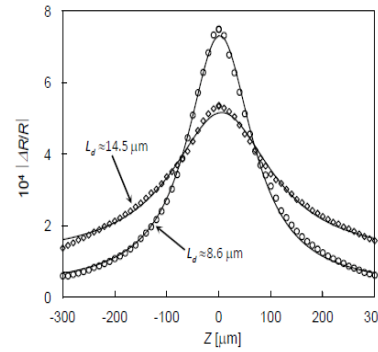
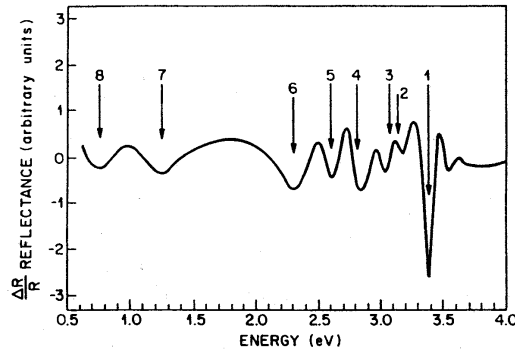
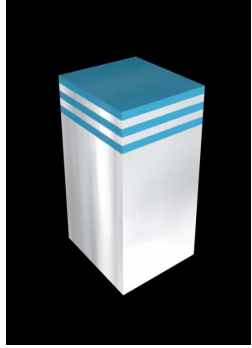
- UV-PES  $\Rightarrow$  large spot size, complex interpretation
- KPFM  $\Rightarrow$  should work in principle...

KPM is  $V_t$ : no metrology

Images courtesy

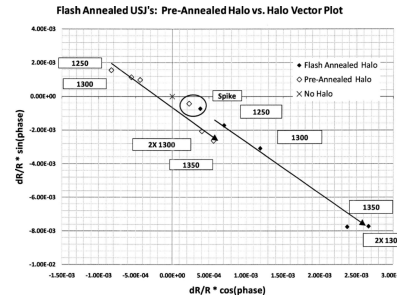
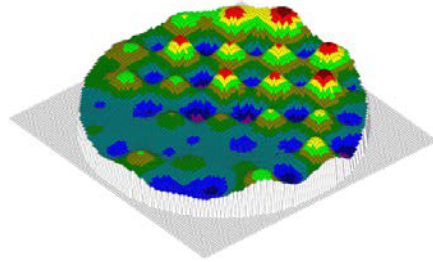
# Photo-Modulated Reflectance (PMR) for GAA:

NS  
epi



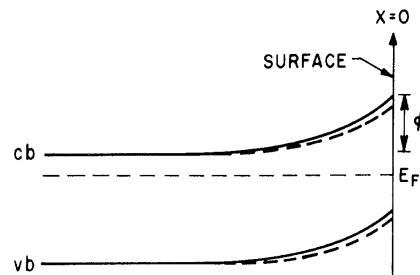
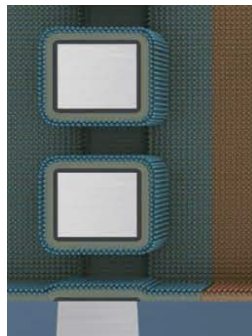
PMR for band-structure analysis & carrier diffusion: SL &  $\mu$  metrology

S/D  
epi



PMR signal directly proportional to  $N_e$ : doping metrology

Metal  
Gate



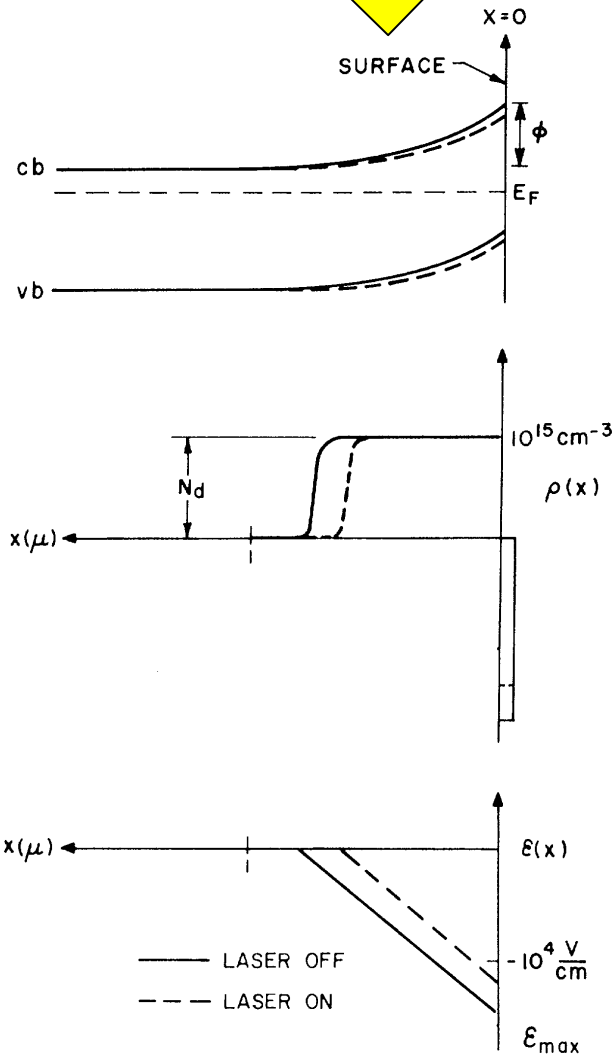
PMR very sensitive to surface capacitance (dipole):  $V_t$  metrology

Images courtesy

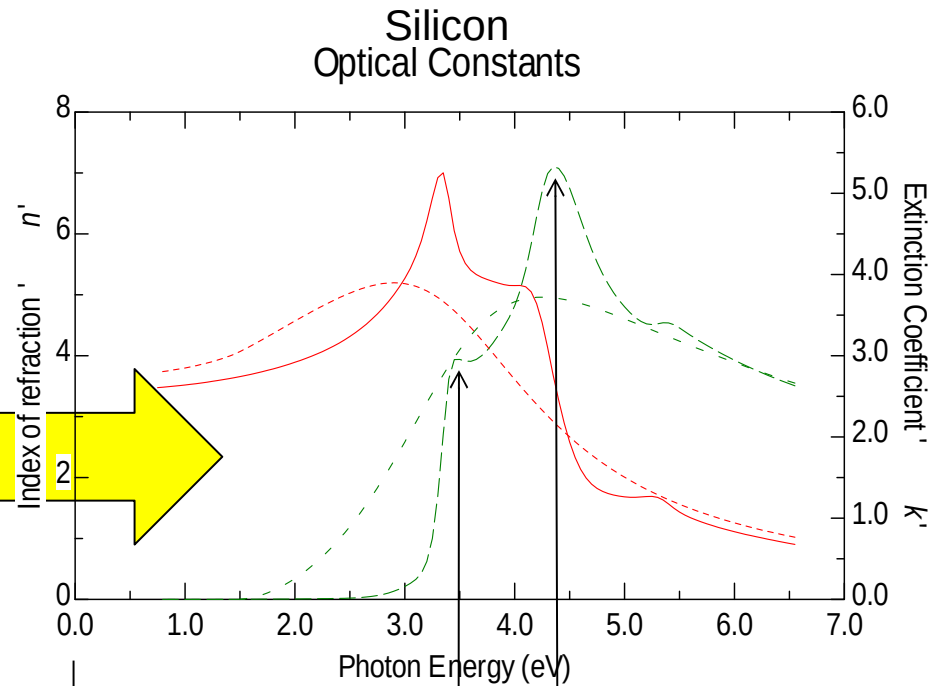


# PMR Principles:

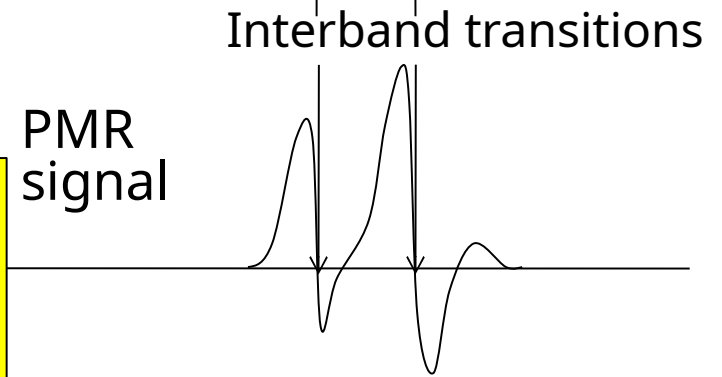
1. Pump beam modulates the sample charge/E-field/voltage



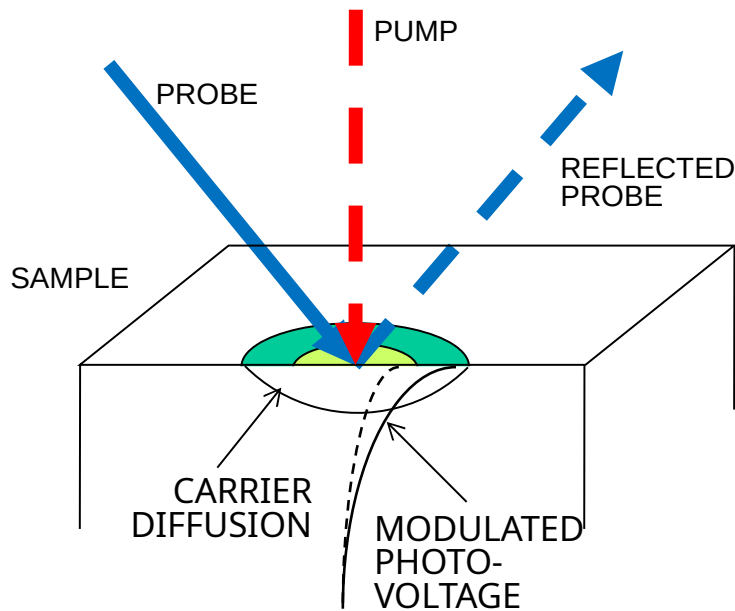
2. Modulated E-field causes reflectivity modulation



3. Probe beam measures the modulated reflectance



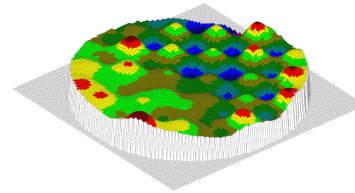
# PMR Capabilities:



Measurement Signal:

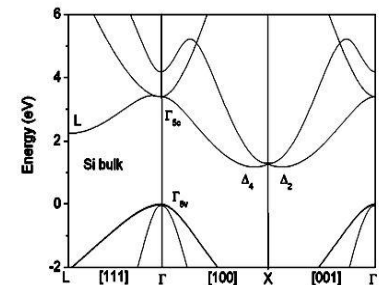
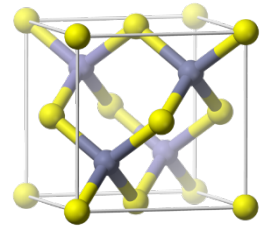
$$\frac{\Delta R}{R} = \frac{2qN_e \Delta V}{\epsilon_s} \times L(\lambda)$$

Carrier Density



Modulated Photo-Voltage

Band-structure



## In-line Criteria:

- Non-contact
- High Sensitivity
- High Speed
- Local

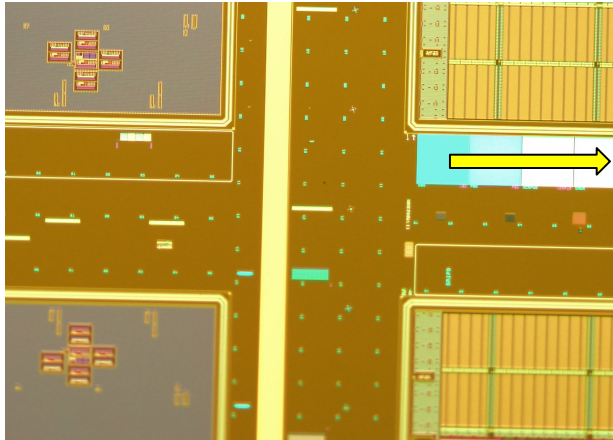
## PMR:

- Non-contact (optical)
- Direct sensitivity to Material Properties
- Measurement time ~seconds
- Micron resolution

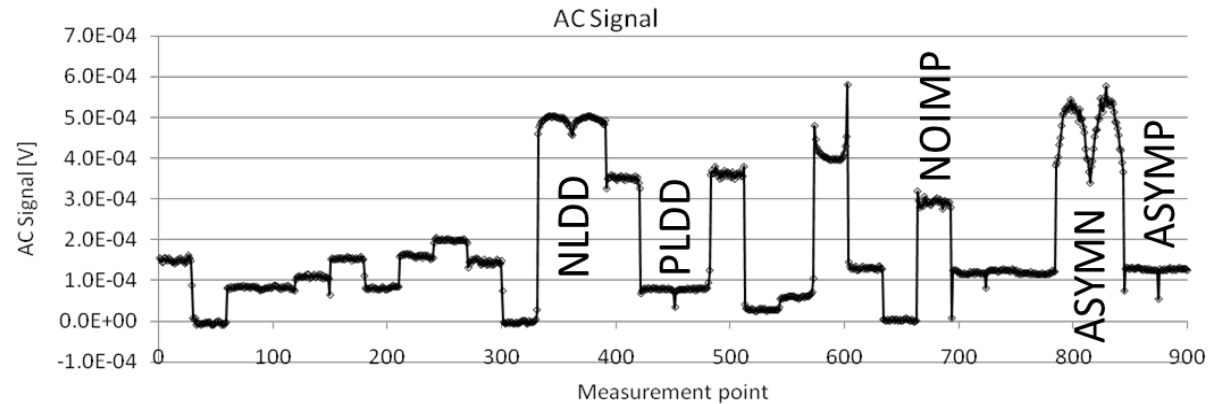
PMR Ideal for GAA Metrology



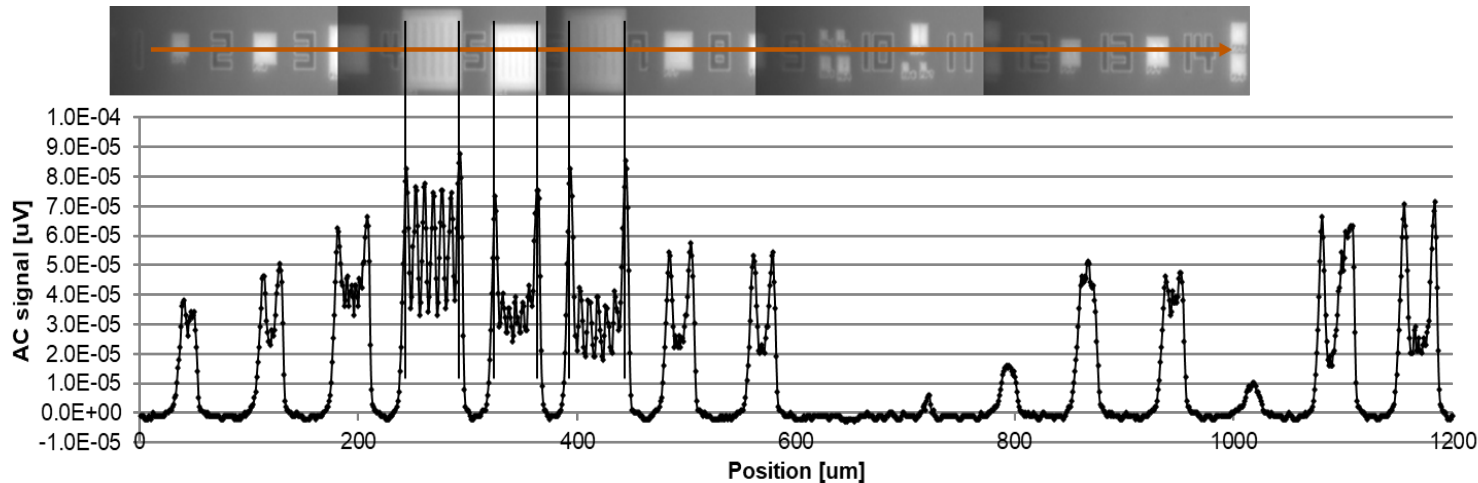
# Example: PMR Carrier Activation



- SIMS boxes on SOI at “Major Foundries”
- MAM time ~4 sec; Spatial res ~  $\mu\text{m}$



- Epitaxial SiGe test structures at Taiwan foundry...



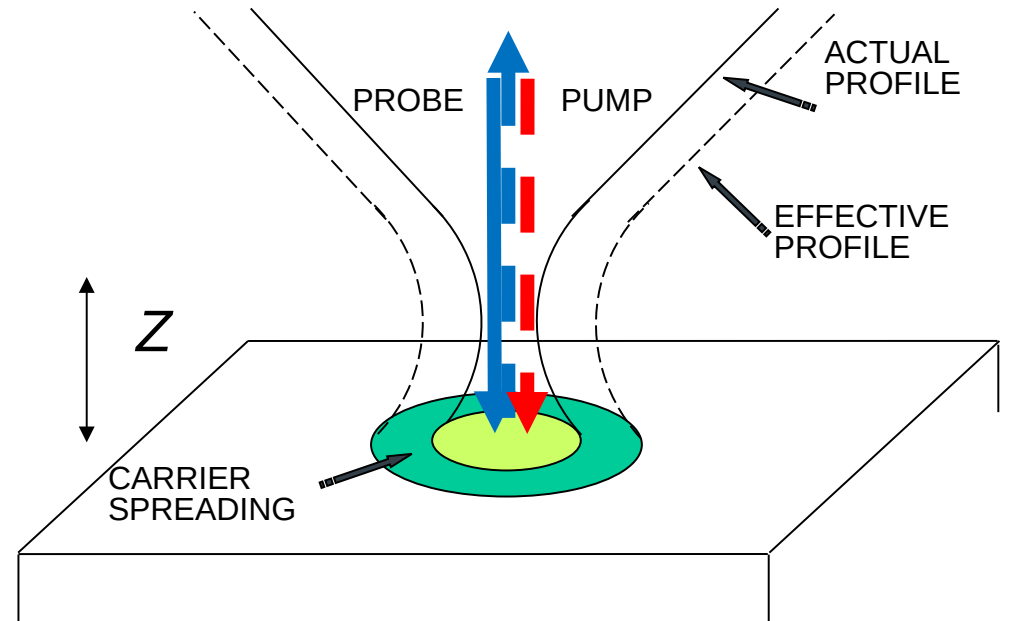
- Background free
- 1-2% Precision
- PR signal ideal for SPC/APC
- $\langle R \rangle$  provides filmstack info

# Example: Z-Scan PMR for Carrier Transport

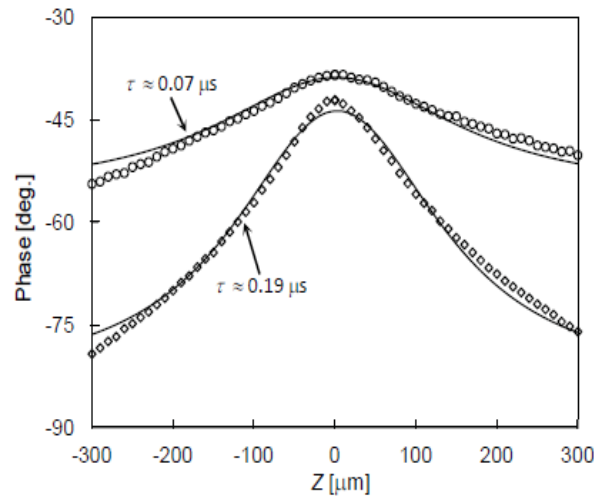
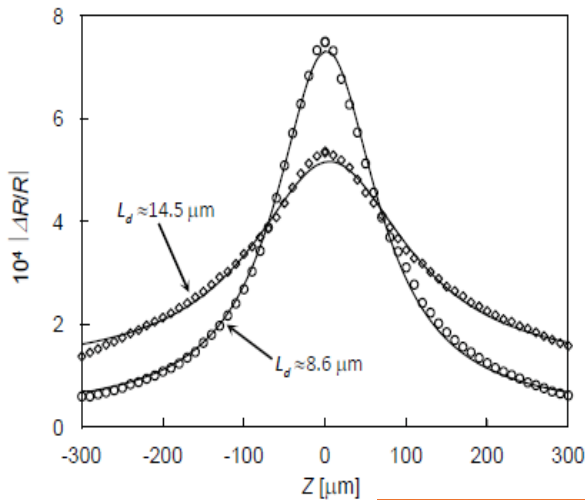
Measurement Signal:

$$\frac{\Delta R}{R} = \frac{A \exp i\phi_0}{\omega^2(Z) + \omega_p^2(Z) + \tilde{L}_d^2}$$

Diffusion Length



Z-Scan PMR data & fit:



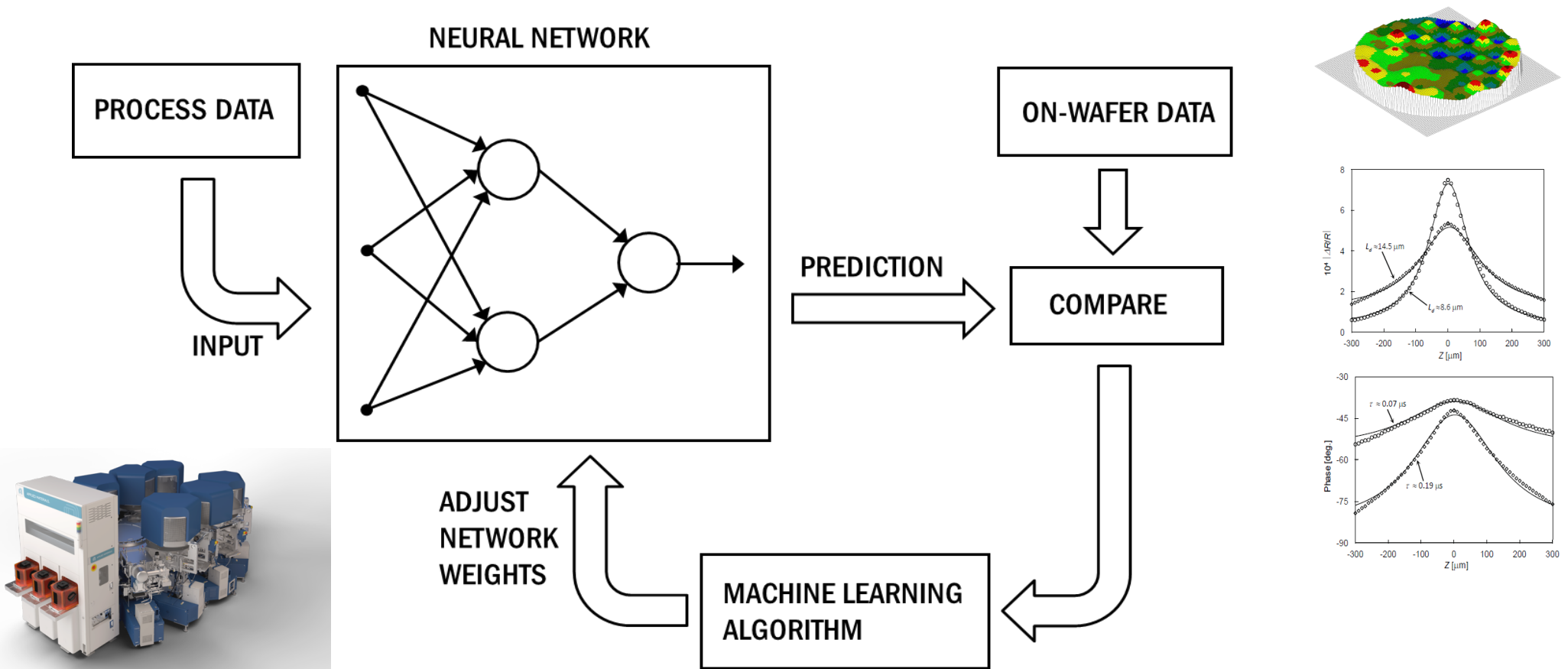
Z-scanning PMR  
yields All-Optical  
Carrier Transport  
Metrology!!

Journal of  
Applied Physics

Xcalipr

# Process Tool Control Using PMR Data:

Process parameters + ML engine + metrology tool:



PMR provides ground truth for prediction from tool/sensor data...

